

Integrated Power Conversion and Power Management Next generation technology for emerging business opportunities

A User's Perspective on GaN and Silicon Power Devices for Integrated / Miniaturized Power Management



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From Appulse Power

• Ahsan Zaman, Aleks Radic, and Behzad Mahdavikhah

From Point the Power

• Alex Avron

Valuable material from

- Texas Instruments and Infineon, APEC 2016
- MIT, Powersoc 2014
- Transphorm, ExxonMobil, TI, EETimes online material



Appulse Power Inc.





www.appulsepower.com www.appulsepower.com/careers www.linkedin.com/appulsepower

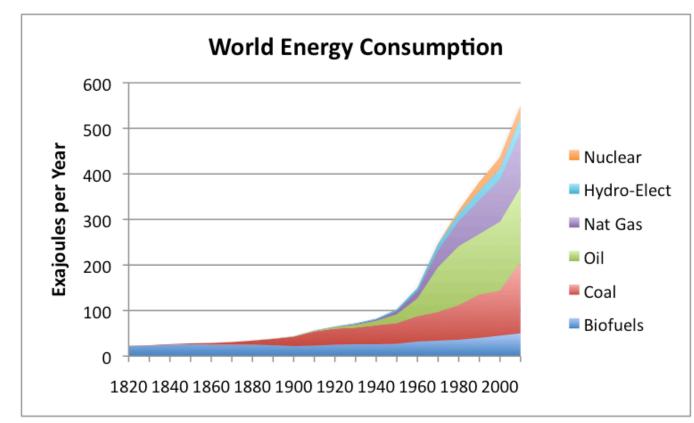


- Founded by PhDs from the U of Toronto in January 2015
 - 'UofT Laboratory for Power Management and Integrated Switch-Mode Power Supplies.'
- Develops ICs, reference designs, and adapters
- Disruptive innovations in:
 - Power conversion topology
 - Control
 - Semiconductors
- Achieves the thinnest form factor for ac/dc converters and highest efficiency across load range
- Supports programmable output without compromising efficiency





• We have entered an era of never-ending need for energy



Ourfiniteworld.com

World Energy Consumption by Source, Based on Vaclav Smil estimates from Energy Transitions: History, Requirements and Prospects together with BP Statistical Data for 1965 and subsequent

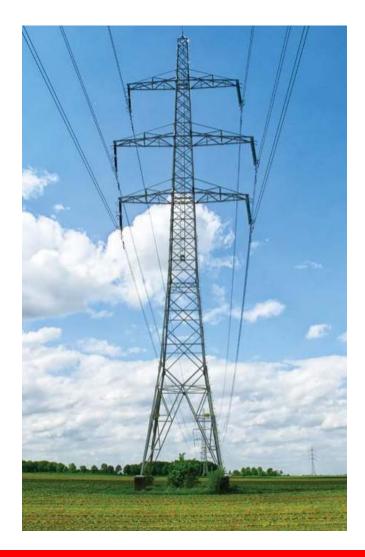


The Need For Power



Thomas Edison probably could not have envisioned all the ways people would use electricity in the 21st century.

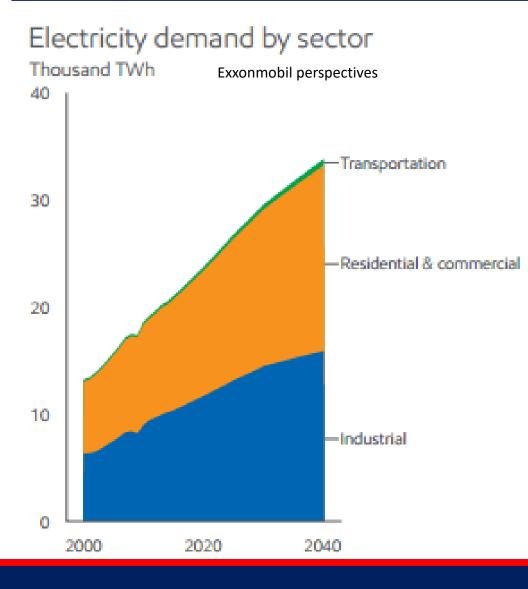
- Electricity powers the factories that make the world's goods. It provides light, heat and air conditioning for homes and commercial buildings.
- Electricity runs the Internet and everything that connects to it.
- Global demand for electricity is expected to rise by 65 percent from 2014 to 2040. Exxonmobil perspectives





The Need For Power





- Demand for electricity to more than double by 2040 !
- Residential & commercial use comparable to industrial use, both growing rapidly.
- <u>Quite possibly a major under</u> <u>estimation</u>
 - It is hard to predict what IoT will look like in 2040

Fundamental Properties of Power Semiconductors



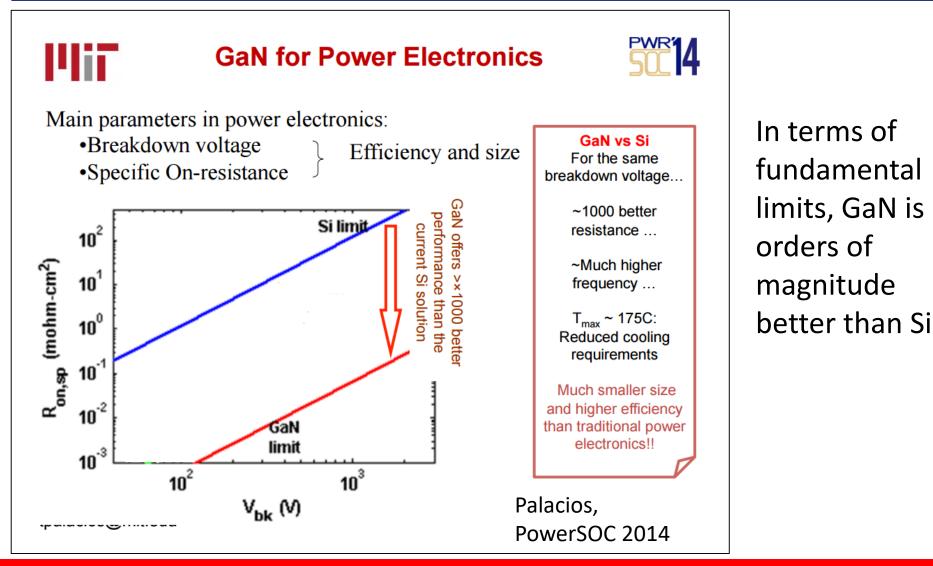
Device property	Si	GaN
Band gap energy, Eg (eV)	1.1	3.42
Electric breakdown field, E _{crit} (10 ⁶ V/cm)	0.3	2 (epi) 3.3 (bulk)
Relative dielectric constant, ϵ_r	11.9	9
Thermal conductivity, k (W/K·cm)	1.5	1.3 (epi) <mark>2.3</mark> (bulk)
Electron mobility, μ _e (cm²/V·s)	1350	1150 2000 for 2DEG
Saturation velocity, v _{sat} (10 ⁷ cm/s)	1	3

GaN outperforms Si in almost every metric for a power device



Fundamental Properties of Power Semiconductors





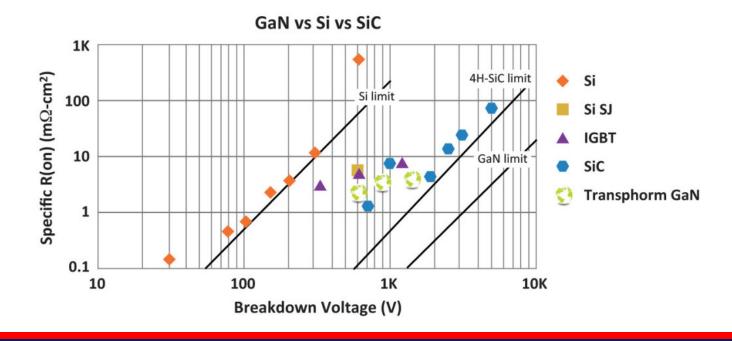


Fundamental Properties of Power Semiconductors





Silicon-based power transistors are reaching limits of operating frequency, <u>breakdown voltage</u> and <u>power density</u> in the power electronics industry and GaN's performance is beginning to shine. By no means is silicon going extinct, but energy requirements are continuing to increase, thereby requiring new methods and materials to be investigated/used to meet these demands.





Comparison of 600V E-mode GaN and SJ-MOSFETs

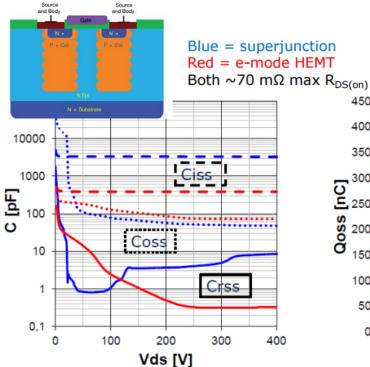


Parameter	E – Mode GaN	SJ-MOSFET	Comments
Vdss	600 V	600 V	
Rdson	52 m Ω	52 m Ω	
R	1.0	0.77	Package dependent
Tk Rdson (150C/25C)	1.8	2.37	
Qg	6 nC	68 nC	10x lower gate charge
Qrr (Qoss)	44nC	6000 nC	100x lower
Со	110 pF	1050 pF	10x lower
Eoss	7 uJ	8 uJ	Near parity hard switching performance

"GaN in a Silicon world: competition or coexistence?" Tim McDonald, Infineon, APEC 2016, Long Beach, California

Fundamental Properties of Power Semiconductors





- 450 12 400 10 350 250 200 150 8 Eoss [µJ] 6 150 100 2 50 0 0 100 300 400 200 Vds [V]
- Output charge difference is very large (up to 10x at 100 V) between superjunction and GaN
- But gap in E_{oss} is much smaller (eg: 20% at 400 V)

Co(tr) of GaN device is ~10x lower than SJ FET; this benefit can be leveraged in <u>ZVS</u> <u>applications</u> where it can result in lower power losses

Qrr >100x lower for GaN devices: this can be leveraged in choice of <u>topology</u> and application

- Superjunction capacitances are much higher when compared to GaN
- Superjunction C_{oss} and C_{rss} behave very nonlinearly with voltage

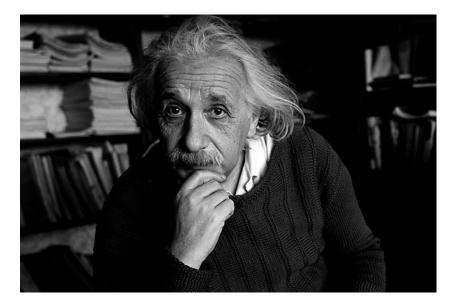
"GaN in a Silicon world: competition or coexistence?" Tim McDonald, Infineon, APEC 2016, Long Beach, California

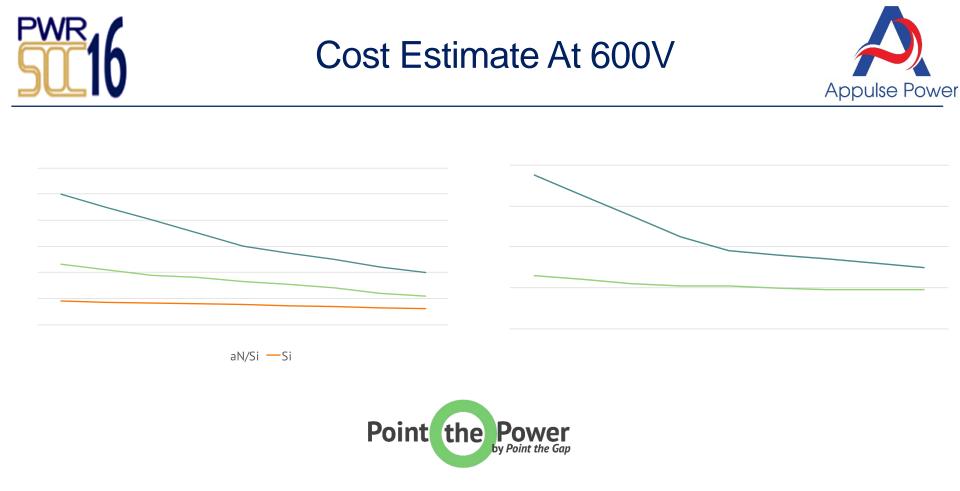




If GaN significantly outperforms Si as a power device, Why does it not have widespread adoption already?

- Cost?
- Reliability / usability?
- Availability?
- Something else?





- Adoption of GaN process and high volume manufacturing will drive cost erosion
 - TSMC now fully part of the GaN manufacturing supply-chain.
- Clear advantage for e-mode versus cascode when going to lower current.

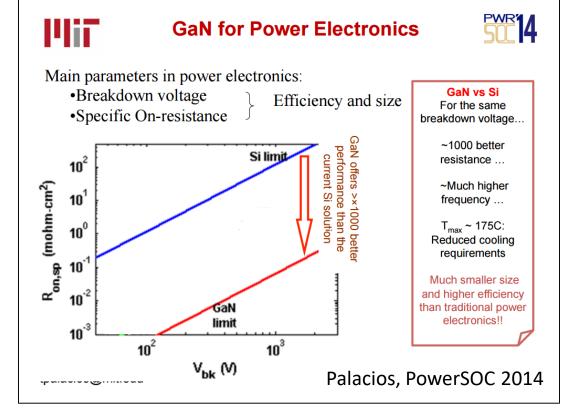
PWR SUC	6	GaN, SiC and Silicon price trends					Appulse Power	
Point the Power					\$			
		Wafer size	Wafer cost	Processed Wafer Cost	Device Cost 600V/10A	Price evolution points ranking		
	Silicon SJ MOSFET	8"	200 USD - 250 USD	400 USD _ 500 USD	0.8\$	 Process cost Shrink of die size Substrate cost 		
_	GaN HEMT	6"	400 USD _ 500 USD	700 USD _ 800 USD	1.6\$	 GaN Epi. Cost Manufacturing Yie GaN Epi. Yield Package cost 	eld	

- SiC cost is starting from very high and dropping faster. But we don't expect to see it being in competition with GaN ٠ and Si on this voltage/current range. GaN will become affordable with production volume, but not directly competitive with Silicon based devices.
- Traction for GaN from Power electronics markets will come from systems designers which will make savings on passives. A. Avron, Point the Power





- If a technology is 1000x better and 2x more expensive, cost can not be a barrier to its adoption
- eGan on Si wafers is not 1000x better than comparable Si transistors, but they are still much better
 - The benefits are topology specific and requires innovation at the circuit level

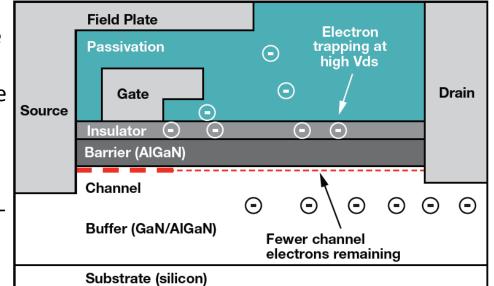


• Cost is one factor, but it should be easily absorbed in other savings at the system level





- GaN HEMTs can suffer from dynamic Rds-on increase aka "current-collapse", caused by negative charge trapping in both the buffer and topside layers.
- Charge can be trapped when high-voltage is applied on the drain, and may not dissipate instantaneously when the device is turned on.
- The trapped negative charge repels electrons from the channel layer, and Rdson increases (the number of electrons in the channel layer is reduced).



Decreases efficiency and can cause the device to excessively self-heat and fail prematurely.
 The trap density can increase as the device ages, making the dynamic Rds-on effect worse.

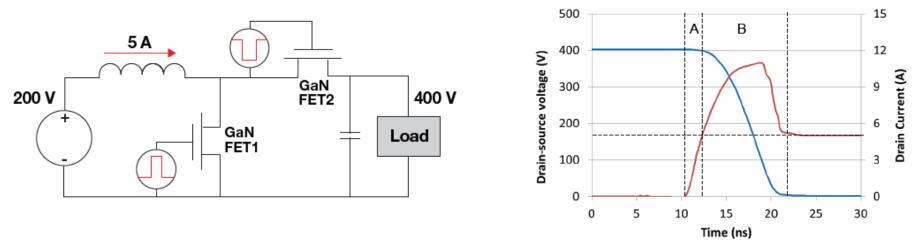
Sandeep R. Bahl, "A comprehensive methodology to qualify the reliability of GaN products" GaN Reliability, TI

J. Joh, N. Tipirneni, S. Pendharkar, S. Krishnan, "Current Collapse in GaN Heterojunction Field Effect Transistors for High-voltage Switching Applications" International Reliability Physics Symposium (IRPS), p. 6C.5.1, 2014. O. Hilt, et. al, "Impact of Buffer Composition on the Dynamic On-State Resistance of High-Voltage AlGaN/GaN HFETs," International Symposium on Power Semiconductor Devices and ICs, p. 345, 2012





- Simulation results of the hard-switching turn-on transition on the primary switch (FET1) are shown for a simple boost topology.
- The input voltage is 200V and the inductor current is 5A.



- When FET1 is off, its drain voltage is clamped at about 400V due to the conduction of the clamp FET (FET2).
- When FET1 turns on, it needs to sink the full inductor current before Vds starts dropping (A).

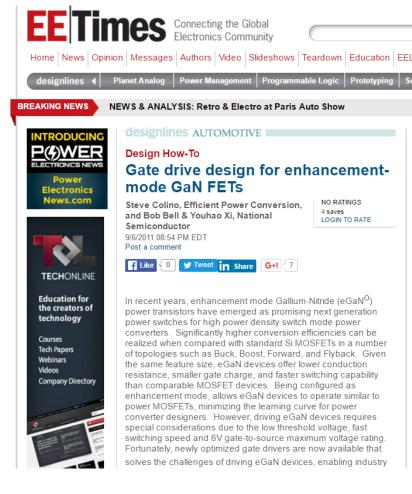
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GaN Reliability – Gate Drive



Gate reliability of GaN often receives concern / attention



Driving eGaN devices requires special considerations due to the low threshold voltage, fast switching speed and 6V gate-to-source maximum voltage rating



UCC27611 SLUSBA5C – DECEMBER 2012–REVISED DECEMBER 2015

UCC27611 4-A and 6-A High-Speed 5-V Drive, Optimized Single-Gate Driver

1 Features

- Enhancement Mode Gallium Nitride FETs (eGANFETs)
- 4-V to 18-V Single Supply Range VDD Range
- Drive Voltage VREF Regulated to 5 V
- 4-A Peak Source and 6-A Peak Sink Drive Current
- 1-Ω and 0.35-Ω Pullup and Pulldown Resistance (Maximize High Slew-Rate dV and dt Immunity)
- Split Output Configuration (Allows Turnon and Turnoff Optimization for Individual FETs)
- Fast Propagation Delays (14-ns Typical)
- · Fast Rise and Fall Times (9-ns and 5-ns Typical)
- TTL and CMOS Compatible Inputs (Independent

3 Description

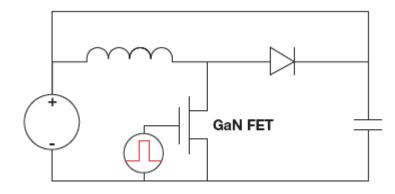
The UCC27611 is a single-channel, high-speed, gate driver optimized for 5-V drive, specifically addressing enhancement mode GaN FETs. The drive voltage VREF is precisely controlled by internal linear regulator to 5 V. The UCC27611 offers asymmetrical rail-to-rail peak current drive capability with 4-A source and 6-A sink. Split output configuration allows individual turnon and turnoff time optimization depending on FET. Package and pinout with minimum parasitic inductances reduce the rise and fall time and limit the ringing. Additionally, the short propagation delay with minimized tolerances and variations allows efficient operation at high frequencies. The 1- Ω and 0.35- Ω resistance boosts immunity to hard switching with high slew rate dV and dt

There are a number of driver ICs as well as options for co-packaging driver circuitry





- Device specific and application specific concerns
- Requires customized stress test and qualification



Test Vehicle for inductive switching application - TI

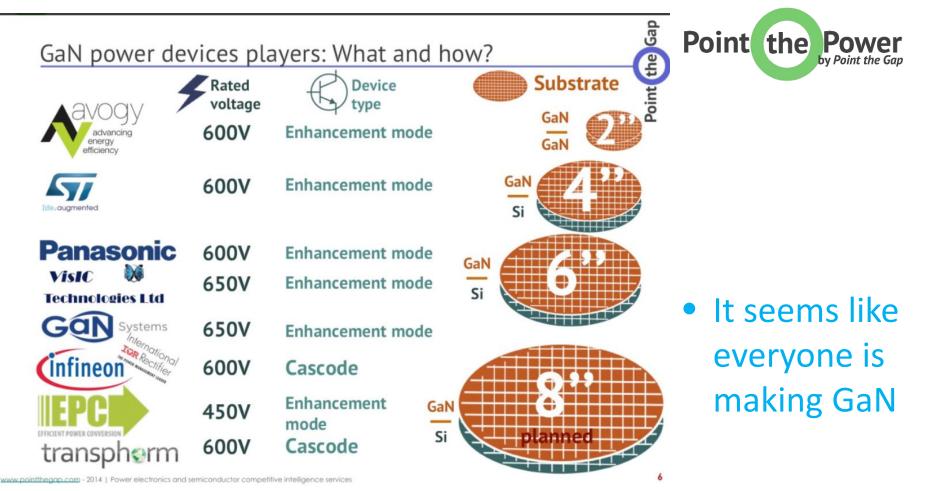
Sandeep R. Bahl, "A comprehensive methodology to qualify the reliability of GaN products" GaN Reliability, TI

Issues are very well understood and not new



GaN Availability





Not all GaN are created equal

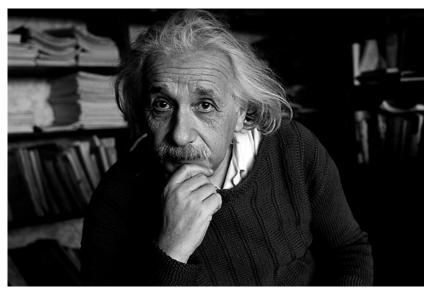




If GaN 1) significantly outperforms Si as a power device, 2) cost is manageable, 3) reliability issues are well understood and controlled, 4) and is widely available

Why does it not have widespread adoption already?

- Cost
- Reliability / usability
- Availability
- Something else





People / Talent



Even before we talk about the <u>adoption of a new semiconductor</u> with unique reliability, tricky gate drive design, and cost sensitivity

- Power electronics engineers are hard to find
- Power electronics engineers with IC design skills are harder to find

How about change?

- Engineers take pride in doing more with less
- Would rather use a lower cost device that has proven the test of time and is in abundance







Even before we talk about the <u>adoption of a new semiconductor</u> with unique reliability, tricky gate drive design, and cost sensitivity

- Power electronics engineers are hard to find
- Power electronics engineers with IC design skills are harder to find
- Power designers with low risk aversion and openness to change is even harder to find







Even before we talk about the <u>adoption of a new semiconductor</u> with unique reliability, tricky gate drive design, and cost sensitivity

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Once You Take The Leap





GaN has to potential for increasing power conversion efficiency:

Reduced power losses & electricity

Less materials such as plastic

Reduced carbon foot print

$GaN \rightarrow GreeN$









- Energy and electricity consumption is increasing in an unprecedented and unsustainable rate
- When realized in its full potential GaN is an enabler of very high efficiency power conversion
 - This requires the use of topologies that can fully leverage GaN's FOMs
- Cost, reliability, and availability are often cited barriers to GaN adoption
 - Increased awareness and education are needed
- High efficiency ac/dc conversion will help toward a greener future

Thank you.